PLASMA ARRAY (LARGE AREA) - MA6000Y-023BC

Categories: Plasma components



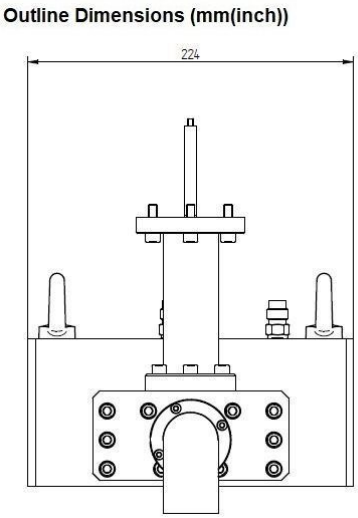
BESCHREIBUNG

A combination of duo-plasmalines can be used to obtain a two dimensional plasma array. Single sources as well as 2, 4 and 8 parallel arranged plasmalines are available for plasma assisted surface treatment like surface activating, etching and deposition.

- Low pressure mirowave plasma source
- Suitable for cleaning, etching, ashing, deposition, sterilization, pretreatment
- Compact design
- Easy adaption to customer systems
- Integrated gas shower
- High plasma density
- High efficiency

BILDERGALERIE





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ADDITIONAL INFORMATION

Typ	Plasma array (large area)
Process	Etching & Deposition
Output Connection Type	Plasma area 797,5 mm x 150 mm
Dielectric material	Ceramics
Output Power [W]	2x 3000
Frequency [MHz]	2450
Gas manifold	Double

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